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For:

A POSITIVE RESIST COMPOSITION

## PRELIMINARY AMENDMENT

Assistant Commissioner for Patents Washington, DC 20231

April 96, 2007 1700 ECE

Sir:

The following preliminary amendments and remarks are respectfully submitted in connection with the above-identaried application.

## In the Specification:

Please replace the paragraph beginning on page 9, line 2, with the following rewritten paragraph:

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The positive resist composition of the present invention comprises the novolac resin described above, quinonediazide compound and the thioxanthone compound as the essential ingredients. In addition, the positive resist composition of the present invention may comprise a resin other than the novolac resin, as well as a small amount of various additives conventional in this field, such as a dye, a surfactant and the like, as